ABSTRACT

PLASMA OUTPUT MONITORING SYSTEM

In a method for monitoring a plasma output from a plasma device used to clean an object, a first wavelength of light emitted by the plasma output to be monitored is identified and an intensity of the first wavelength of light is sensed. A second wavelength of light emitted by the plasma output is also identified to be used as a baseline, and an intensity of the second wavelength of light is sensed. The intensities of the first and second wavelengths of light are then compared to determine whether their relationship falls within an acceptable threshold.

(FIG. 2)